

L Number	Hits	Search Text	DB	Time stamp
-	215	polysilicon same (pores asperit\$3)	USPAT	2003/03/19 11:07
-	5677	mask near3 alignment	USPAT	2003/03/19 11:06
-	3996	(mask near3 alignment) and etch\$3	USPAT	2003/03/19 10:34
-	479	(mask near3 alignment) and etch\$3 near2 (poly polysilicon)	USPAT	2003/03/19 11:07
-	56	((mask near3 alignment) and etch\$3 near2 (poly polysilicon)) and mark\$1	USPAT	2003/03/19 11:06
-	4522	mask near3 alignment	US-PGPUB; EPO; JPO; DERWENT	2003/03/19 11:07
-	0	(mask near3 alignment) and mark\$1 and etch\$3 near2 (poly polysilicon)	USPAT	2003/03/19 11:07
-	9	(mask near3 alignment) and mark\$1 and etch\$3 near2 (poly polysilicon)	US-PGPUB; EPO; JPO; DERWENT	2003/03/19 11:07
-	2485	438/703,704,706,712,719,720,723,724.ccls.	USPAT	2003/03/19 11:08
-	342	438/703,704,706,712,719,720,723,724.ccls. and ion near implantat\$3	USPAT	2003/03/19 11:10
-	338	(438/703,704,706,712,719,720,723,724.ccls. and ion near implantat\$3) and etch\$3	USPAT	2003/03/19 11:10
-	7666	430/311-314,323-326,329,281.1.ccls.	USPAT	2003/03/19 11:09
-	414	216/47.ccls.	USPAT	2003/03/19 11:10
-	7940	430/311-314,323-326,329,281.1.ccls. 216/47.ccls.	USPAT	2003/03/19 11:10
-	454	(430/311-314,323-326,329,281.1.ccls. 216/47.ccls.) and ion near implantat\$3	USPAT	2003/03/19 11:10
-	435	((430/311-314,323-326,329,281.1.ccls. 216/47.ccls.) and ion near implantat\$3) and etch\$3	USPAT	2003/03/19 11:10
-	419	((430/311-314,323-326,329,281.1.ccls. 216/47.ccls.) and ion near implantat\$3) and etch\$3) not (438/703,704,706,712,719,720,723,724.ccls. and ion near implantat\$3) and etch\$3)	USPAT	2003/03/19 11:15
-	1	("6200903").PN.	USPAT	2003/03/19 11:15
-	5	("4068018" "4253888" "4321317" "5009720" "6001739").PN.	USPAT	2003/03/19 11:15